

CLAIMS

We claim:

1. An abrasive slurry for the planarization of a low dielectric constant surface comprising abrasive particles having a hardness comparable to the hardness of said surface,
5 wherein said abrasive particles have a surface charge opposite to that of said surface.
2. An abrasive slurry as in Claim 1 wherein said abrasive particles are polymers.
- 10 3. An abrasive slurry as in Claim 2 wherein said abrasive particles are selected from the group consisting of polystyrene-acrylonitrile, Nylon-6, polyoxymethylene, polyurethane and poly(para-divinylphenylene) and mixtures thereof.
- 15 4. An abrasive slurry as in Claim 1 wherein said abrasive particles comprise a coating on a core wherein said coating material is softer than said core material.
- 20 5. A method of planarizing a low dielectric constant surface comprising performing a conventional chemical mechanical planarization followed by buffing with an abrasive slurry wherein said abrasive slurry has a hardness less than or comparable to the hardness of said surface.

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